



UNITED STATES PATENT AND TRADEMARK OFFICE

BIBDATASHEET

CONFIRMATION NO. 1185

RULE APPLICANTS Jae Chang Jung, Ichan-shi, KOREA, REPUBLIC OF: Keun Kyu Kong, Ichan-shi, KOREA, REPUBLIC OF: Min He Jung, Ichan-shi, KOREA, REPUBLIC OF: CONTINUING DATA This application is a CIP of 09/465, 111 12/18/1999 ABN STL FOREIGN APPLICATIONS REPUBLIC OF KOREA 98-63793 12/31/1998 STL FREQUIRED, FOREIGN FILING LICENSE GRANTED COUNTRY KOREA, REPUBLIC OF: COUNTRY KOREA, REPU	800 Octo Sheet				,	-		MINUN 110, 11
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